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Patent

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE.

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In re Application of:)				
	Han-Ming Wu et al.	Examiner: Nguyen, Hung	WINDICK			
Serial No:	09/752,938) Art Unit :	A system of			
Filed:	December 29, 2000)				
For: Purging Gas from a Photolithography Enclosure Between a Mask Protective Device and a Pattern Mask))))				
RESPONSE TO OFFICE ACTION						
	e Amendment					

Assistant Commissioner for Patents Washington, D.C. 20231

Sir:

In response to the Office Action mailed April 29, 2002 the Applicants respectfully request the Examiner to enter the following amendments and to consider the following remarks.

FIRST CLASS CERTIFICATE OF MAILING

I hereby certify that I am causing the above-referenced correspondence to be deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated below and that this paper or fee has been addressed to the Assistant Commissioner for Patents, Washington, D. C. 20231

	9, 2002		
Date of	f Deposit		
Debbie Pelo	quin		
Name of Person Ma	iling Correspondence		
bby Pulcquin Signature	July 29, 2002	Date	ECHN

Docket No.: 42390P10058 Application No.: 09/752,938

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